

New!

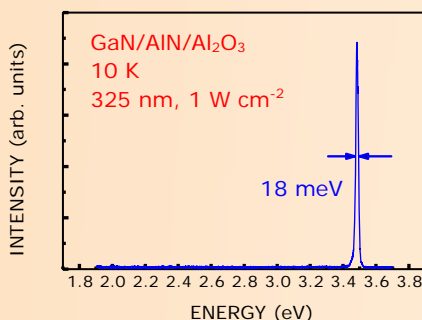


MBE SYSTEM FOR III-NITRIDES

Modular, expandable and successful

Designed by **CreaTec**, the state-of-the-art MBE system for III-nitrides combines standard MBE growth techniques using a nitrogen plasma source with CVD growth techniques based on a special ammonia source. The chamber design is optimized for the usage of ammonia using a special cryoshroud with a unique pumping system for a high throughput of grown layers.

The results obtained from epitaxial GaN layers are excellent and demonstrate the high performance of the system.



PL spectrum of a 1.7 μm thick GaN layer grown on AlN/Al₂O₃.

Designed and
manufactured by CreaTec
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